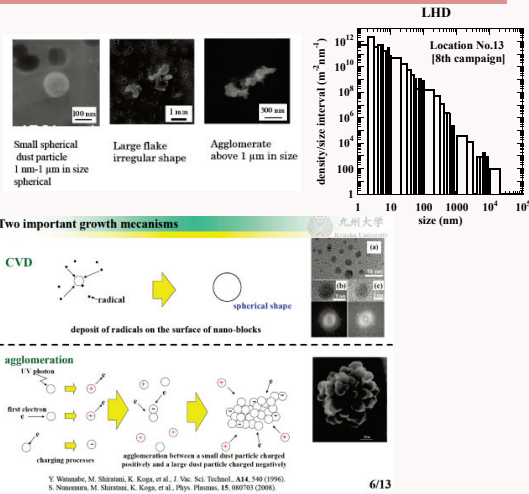


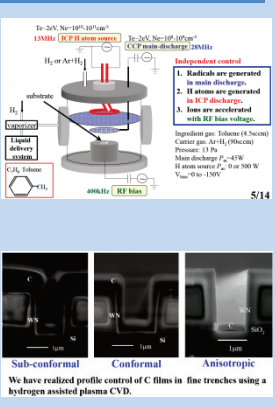
Center of Plasma Nano-interface Engineering (CPNE)

Overview: This center was established in October 1st 2010 to promote innovative research, collaboration with researchers in industry, and worldwide networks for plasma engineering. It consists of four sections: 1) fundamental plasma engineering section, 2) plasma electronics section, 3) plasma environmental engineering section, and 4) plasma bio-engineering section.

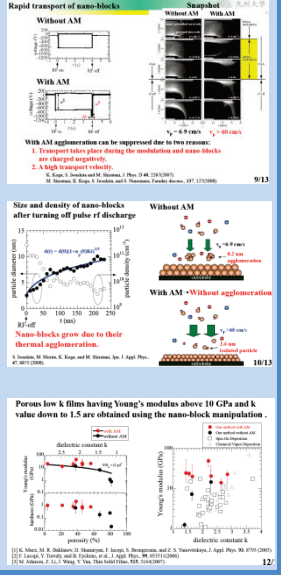
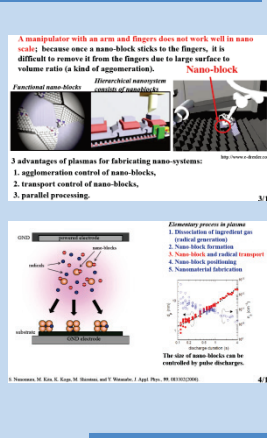
I. Nano-particles produced due to plasma surface interaction



I. Deposition profile control using plasma anisotropic CVD method



II. Nano-particle composite films for Ultra Low-k films



1. Fundamental plasma engineering section

Staff: Assistant Professor Kunihiro Kamataki

Center of Plasma Nano-interface Engineering

2. Plasma electronics section

Staff: Associate Professor Naho Itagaki

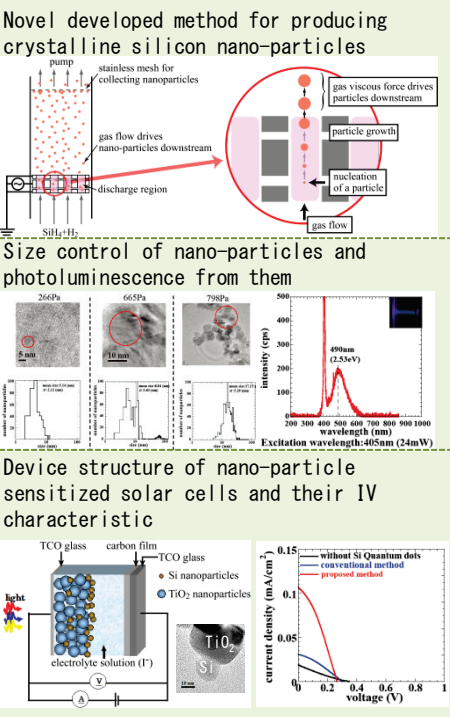
3. Plasma environmental engineering section

Staffs: Distinguished Professor Masaharu Shiratani, Assistant Professor Giichiro Uchida

4. Plasma bio-engineering section

Staffs: Professor Junya Suehiro, Associate Professor Kazunori Koga, Assistant Professor Michihiko Nakano

I. Third generation solar cells



II. High quality thin film Si solar cells

